IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Wen Chin Lin et al. § Group Art Unit: Unknown 8888 Serial No. Unknown Examiner: Unknown Filed: Herewith § For: Non-Orthogonal Write Line Structure In MRAM

INFORMATION DISCLOSURE STATEMENT

Commissioner For Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

In compliance with the duty of disclosure under 37 CFR §1.56, and in accordance with the practice under 37 CFR §1.97 and §1.98, the Examiner's attention is directed to the documents listed on the enclosed modified Form PTO-1449. No inference should be made that the cited references are in fact material, are in fact prior art, or that no better art exists. The cited patents are listed in numerical order and are not in any order based on their pertinence.

The above-identified application is being after June 30, 2003. Therefore, pursuant to the waiver of the requirement under 37 CFR 1.98 (a)(2)(i) as stated in a Pre-OG Notice dated July 11, 2003, copies of only the foreign patent documents and non-patent literature listed on the enclosed modified Form PTO-1449 are attached.

This Information Disclosure Statement is being filed within three months of the United States filing date or before the mailing date of a first Office Action on the merits. No certification or fee is required (37 CFR §1.97(b)).

The Commissioner is hereby authorized to charge any additional fees which may be required or credit any overpayment to Deposit Account 08-1394.

It is respectfully requested that the above information be considered by the Examiner and that a copy of the enclosed Form PTO-1449 be returned indicating that such information has been considered.

Respectfully submitted.

Registration No. 55,272

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File: 24061.90

R-72583.1

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I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to Commissioner For Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on 4-19-04

Bonnie Boyle

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In place of U. S. DEPARTMENT OF COMMERCE PTO-1449 PATENT AND TRADEMARK OFFICE Complete if Known Form Application Number Filing Date Herewith **INFORMATION DISCLOSURE** Applicant(s) STATEMENT BY APPLICANT Wen Chin Lin et al. Art Unit (use as many sheets as necessary) **Examiner Name** SHEET Attorney Docket Number 24061.90 (TSMC2003-0542) OF

U. S. PATENT DOCUMENTS					
Examiner's Initials	Cite No.	Document Number	Publication Date	Name of Patentee or Applicant of Cited Document	
	AA	6,005,800	12-21-1999	Koch et al.	
	AB	6,114,719	09-05-2000	Dill et al.	
	AC	6,335,890	01-01-2002	Reohr et al.	
	AD	6,368,878	04-09-2002	Abraham et al.	
	AE	6,430,084	08-06-2002	Rizzo et al.	
	AF	6,490,217	12-03-2002	DeBrosse et al.	
	AG	6,509,621	01-21-2003	Nakao	
	AH	6,522,579	02-18-2003	Hoenigschmid	
	Al	6,567,299	05-20-2003	Kunikiyo et al.	
	AJ	6,590,803	07-08-2003	Saito et al.	
	AK	6,594,191	07-15-2003	Lammers et al.	
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	AM	6,661,689	12-09-2003	Asao et al.	
	AN	6,667,899	12-23-2003	Subramanian et al.	
	AO	6,693,822	02-17-2004	Ito	
	AP	6,693,826	02-17-2004	Black, Jr. et al.	

FOREIGN PATENT DOCUMENTS							
Examiner's Initials	Cite No.	Foreign Patent Document (Country Code - Number - Kind)	Publication Date	Patentee or Applicant of Cited Document	Translation		

OTHER PRIOR ART					
Examiner's Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article, title of the item, date, page(s), volume- issue number(s), publisher, city/country where published			
	AQ	A. ANGUELOUCH et al., "Two-dimensional magnetic switching of micron-size films in magnetic tunnel junctions", Applied Physics Letters, 31 January 2000, pages 622-624, Volume 76, Number 5, American Institute of Physics			
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Examiner	Date	
Signature	Considered	

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include a copy of this form with next communication to applicant.